

PRESS RELEASE

Lasertec Corporation

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Lasertec Releases PELMIS Series EUV Pellicle Inspection System

Yokohama, December 2, 2024 - Lasertec Corporation announced today the release of the PELMIS Series, an inspection system that detects particles on EUV pellicles¹.

Lasertec has gained recognition from wafer fabs and mask shops worldwide for its timely provision of solutions to various EUV mask inspection needs. In recent years, the expansion of the EUV market has led to an increase in demand for inspection of EUV pellicles. The newly released PELMIS Series detects particles on the surface of pellicles attached to EUV masks and performs automatic classification of whether they are on the front or the back side of the pellicle. PELMIS can also detect particles on the pattern surface and its peripheral areas of EUV masks, making it a useful tool in various applications.

The PELMIS Series is expected to bring optimum productivity to pelliclized EUV mask inspection processes and enable inspection of the entire EUV mask when used in combination with the ACTIS Series Actinic² EUV Patterned Mask Inspection System, the BASIC Series EUV Mask Backside Inspection and Cleaning System and the MZ Series Mask Edge Inspection System.

Lasertec will continue to enhance its lineup of inspection systems to meet the needs of leading-edge semiconductor manufacturers adopting EUV lithography for high-volume manufacturing, thereby facilitating the advancement of the semiconductor industry.

1: Pellicles are protective films attached to masks to prevent particles from falling on them.

2: Actinic is a term that indicates that the light used in inspection has the same wavelength as that of the exposure light used in EUV lithography.

Features

- Inspection of pellicles and automatic classification of whether particles are on the front or back side of pelliclized EUV masks
- Detection of particles on the surface of pellicles as well as the pattern surface and the peripheral area of masks
- Die-to-die inspection and mask-to-mask inspection

Applications

- Detection of particles on EUV pellicles and the pattern surface of masks and periodic quality assurance inspection at wafer fabs
- Quality assurance inspection during EUV mask manufacturing processes at mask shops



PELMIS Series EUV Pellicle Inspection System

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